FILE 'REGISTRY' ENTERED AT 12:23:51 ON 31 AUG 2005

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L1          2368   S    SILICON NITRIDE OR N.SI/MF OR N SI/ELF
L2          5715   S    N/ELS,MAC AND SI/ELS,MAC AND NITRIDE
L3           373   S    NITROUS OXIDE OR N2O/MF
L4            24   S    CH3F/MF
L5         35276   S    FLUOROMETHANE
L6           330   S    L5 AND C H F/ELF
L7           346   S    L4 OR L6
```

FILE 'HCAPLUS' ENTERED AT 12:27:43 ON 31 AUG 2005

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L8           173   S    (L3 OR NITROUS OXIDE OR N2O) AND (CH3F OR
FLUOROMETHANE OR MONOFLUOROMETHANE OR METHYLFLUORIDE OR METHYL FLUORIDE)
L9            28   S    L8 AND (PLASMA OR ?PECVD OR (ELECTRIC##### OR
CHARG#### OR ION##)(3A)GAS#####)
L10            7   S    L9 AND ((L1 OR L2) OR SIN OR SI3N4 OR (SI OR
SILICON)(W)NITRIDE)
L11        23431   S    (L1 OR L2)(L)(BARRIER#### OR BLOCK##### OR
PREVENT#### OR ANTI###### OR AGAINST OR LAYER OR FILM)
L12         4649   S    (L1 OR L2)(L)(ETCH##### OR REMOV##### OR
                EXPOS####)
L13            3   S    L10 AND L11
L14            5   S    L10 AND L12
L15            5   S    (L13 OR L14)
L16            7   S    L10 OR L15
                  D BIB AB HITSTR TOT
                  D ALL HITSTR TOT
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FILE 'REGISTRY' ENTERED AT 12:33:08 ON 31 AUG 2005

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L17           24   S    CH3F/MF
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FILE 'HCAPLUS' ENTERED AT 12:33:30 ON 31 AUG 2005

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L18          200   S    (L8 OR L9 OR L10 OR L11) AND L17
SILICON)(W)NITRIDE)
L19           66   S    L18 AND ((L1 OR L2) OR SIN OR SI3N4 OR (SI
                OR SILICON)(W)NITRIDE)
L20            7   S    L18 AND BARRIER(2A)(LAYER OR FILM)
L21          142   S    L18 AND (L3 OR NITROUS OXIDE OR N2O)
L22           10   S    (L19 OR L20) AND L21
L23            5   S    L22 NOT L16
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